PhotoKleen™EZD-3X Filter Capsules



Data Sheet MEEZD3XENg

Description

The PhotoKleen™ EZD-3X filter is designed for small-volume dispense systems, which have the smallest footprint. The PhotoKleen™ EZD-3X filter has almost double the filter area (compared to the PhotoKleen™ EZD-3 filter) in the same capsule size. This allows for lower pressure drop during filtration or allows the installation of finer filtration at the same pressure drop. Two filter media types are available,

Asymmetric Nylon 6,6 and HDPE. The naturally hydrophilic Nylon 6,6 membrane allows for spontaneous wettability, and its polarity has been shown to lower defectivity on the patterned wafers. The XP option is available for advanced lithography processes.

Features & Benefits

- Double the filter area in the same size capsule (Ref. PhotoKleen™ EZD-3 filter)
- Easy change out style filter assembly
- Two membrane material types available
- Minimized hold-up volume, and top in / top out flow direction with side conduit for laminar filling
- Offers lower pressure drop for higher viscosity fluids
- Reduces tool down time by extending filter change outs
- Optimized media selection for target applications
- Minimized organic extractables by XP option for rapid start-up and reducing chemical wastes.
- XP option guarantees low organic, metal and particle cleanliness for the most advanced processes.



PhotoKleen™ EZD-3X filters are designed to fit into all PhotoKleen™ EZD-3 head manifolds

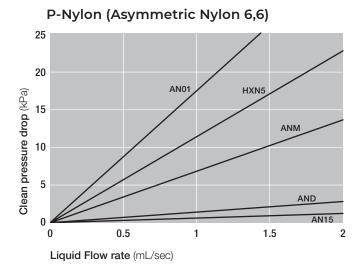
Specifications

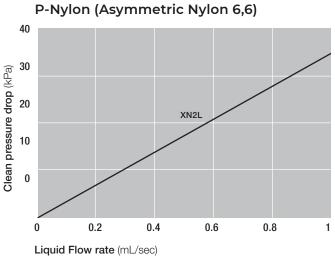
Materials of Construction

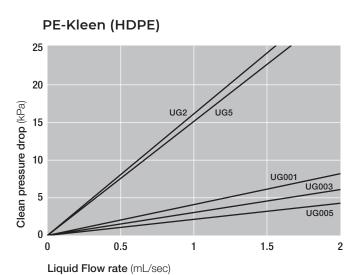
Components	Materials		
Filter Media	P-Nylon: Hydrophilic Asymmetric Nylon 6,6 PE-Kleen: High Density Polyethylene (HDPE)		
Support and Drainage	High Density Polyethylene (HDPE)		
Core, Cage, and End Caps	High Density Polyethylene (HDPE)		
Housing	High Density Polyethylene (HDPE)		
O-ring	Perfluoroelastomer		

Removal Ratings	P-Nylon : 2 nm, 5 nm, 10 nm, 20 nm, 40 nm, 0.15 μm PE-Kleen : 2 nm, 5 nm, 10 nm, 30 nm, 50 nm			
Filter Area	P-Nylon PE-Kleen	: 2 nm 5 nm 10, 20, 40 nm, 0.15 : 2, 5, 10, 30 nm 50 nm		
Maximum Forward Differential	P-Nylon : 0.27 MPa @ 20 °C / 39 psid @ 60 °F PE-Kleen : 0.29 MPa @ 30 °C / 42 psid @ 86 °F			
Maximum Operating Temperature	30 °C / 86 °F			
Maximum Operating Pressure	0.29 MPaG @ 30 °C / 42 psig @ 86 °F			

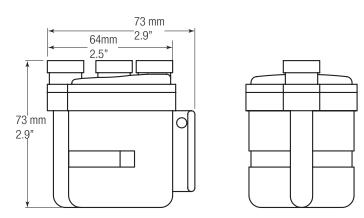
Typical Flow Characteristics - 1cP fluid, 20 °C







Dimensions¹



 $^{^{1}}$ PhotoKleen $^{\text{TM}}$ EZD-3 head manifolds are compatible with PhotoKleen $^{\text{TM}}$ EZD-3X capsules.

Part Numbers / Ordering Information²

PHD12 1 EH11B

Table 1

Code	Filter Media	Removal Ratings	
XN2L ³	P-Nylon	Asymmetric Nylon6,6	2 nm
HXN5 ³		Asymmetric Nylon6,6	5 nm
AN01		Asymmetric Nylon6,6	10 nm
ANM		Asymmetric Nylon6,6	20 nm
AND		Asymmetric Nylon6,6	40 nm
AN15		Asymmetric Nylon6,6	0.15 µm
UG2	PE-Kleen	HDPE	2 nm
UG5		HDPE	5 nm
UG001		HDPE	10 nm
UG003		HDPE	30 nm
UG005		HDPE	50 nm

² For XP option add –XP to end of part number for 10 nm / 20nm removal ratings.

Caution: For optimal filtration performance, it is recommended to replace your filters at-least once a year. Annual replacements will reduce the potential of any leakages that may result due to prolonged chemical exposure. Pall warrants its filters for a period of 1 year from the date of shipment.



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 $\label{eq:pall-conjugate} Pall Corporation has offices and plants throughout the world. To locate the Pall office or distributor nearest you, visit www.pall.com/contact.$

The information provided in this literature was reviewed for accuracy at the time of publication. Product data may be subject to change without notice. For current information consult your local Pall distributor or contact Pall directly.

IF APPLICABLE Please contact Pall Corporation to verify that the product conforms to your national legislation and/or regional regulatory requirements for water and food contact use

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 $^{^3}$ XP treatment is standard on 2 nm / 5 nm removal ratings.